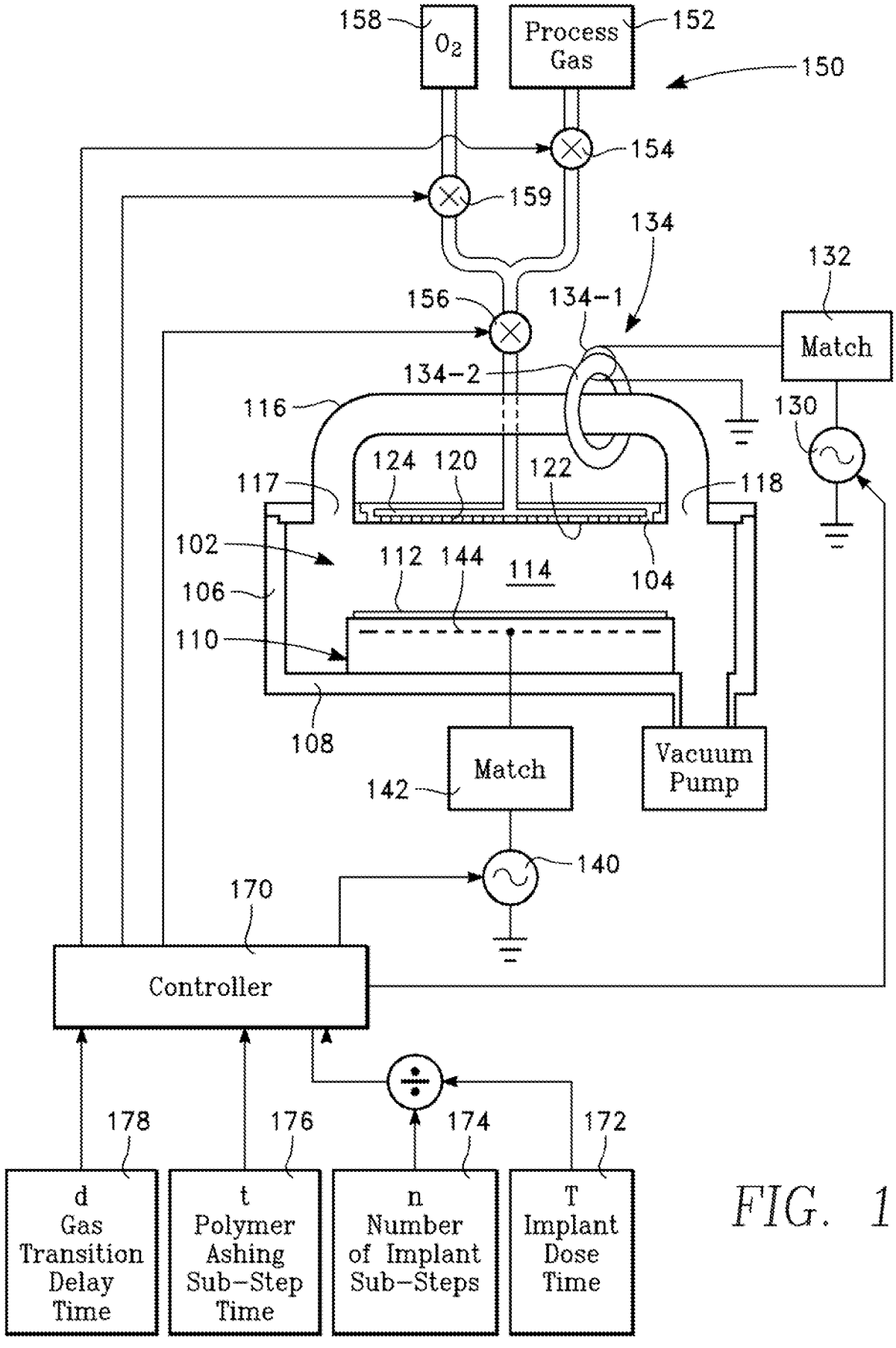

158
O_2
Process Gas
152
150
154
159
134
132
156
134-1
Match
134-2
116
130
124
120
122
117
118
102
112
144
114
104
106
110
108
Match
142
Vacuum Pump
140
170
Controller
178
176
174
172
d
Gas Transition Delay Time
t
Polymer Ashing Sub-Step Time
n
Number of Implant Sub-Steps
T
Implant Dose Time

FIG. 1

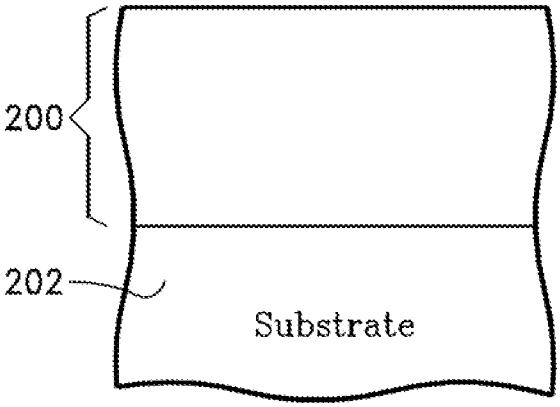


FIG. 2A

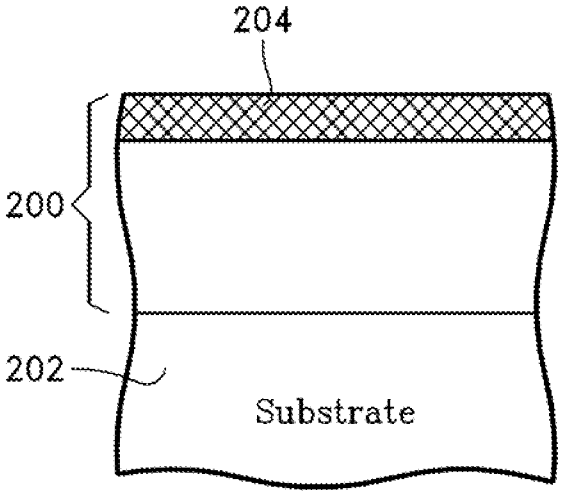


FIG. 2B

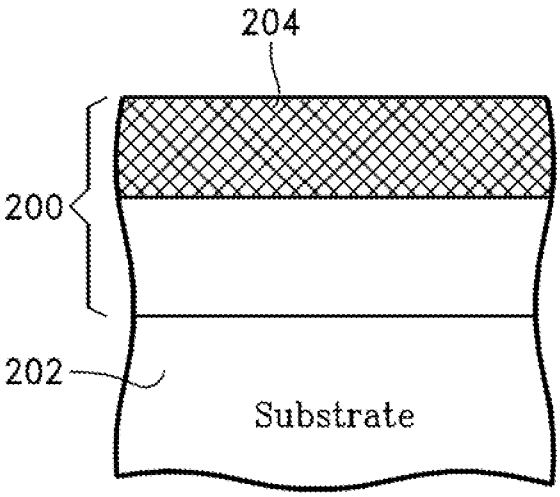


FIG. 2C

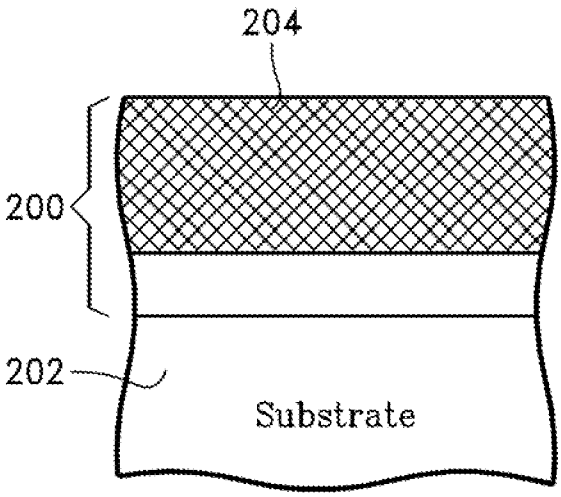


FIG. 2D

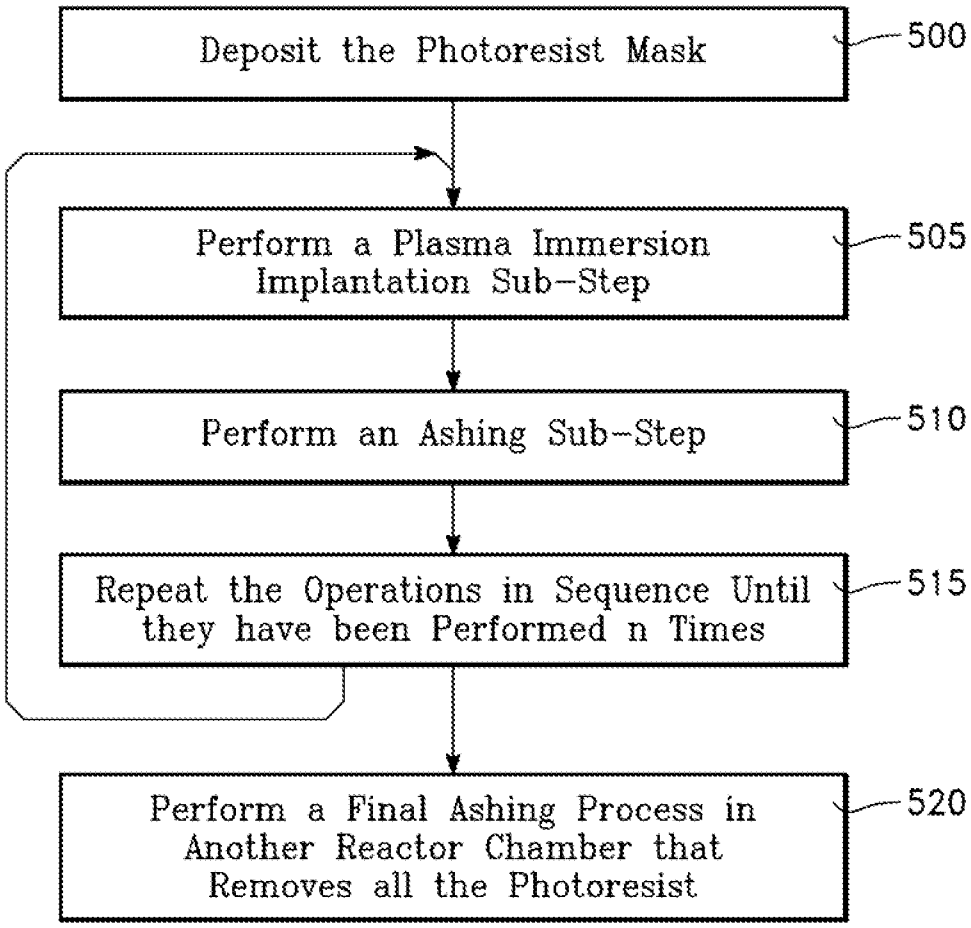

Deposit the Photoresist Mask
500
Perform a Plasma Immersion Implantation Sub-Step
505
Perform an Ashing Sub-Step
510
Repeat the Operations in Sequence Until they have been Performed n Times
515
Perform a Final Ashing Process in Another Reactor Chamber that Removes all the Photoresist
520

FIG. 3

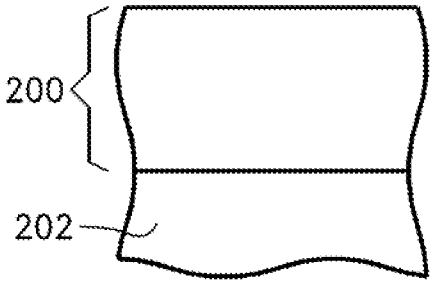


FIG. 4A

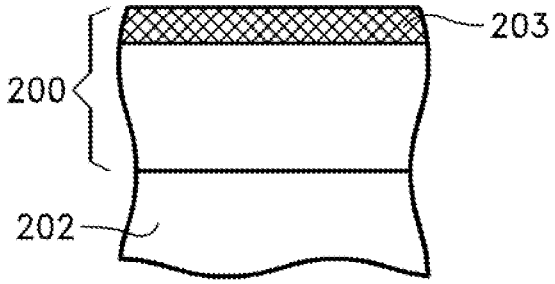


FIG. 4B

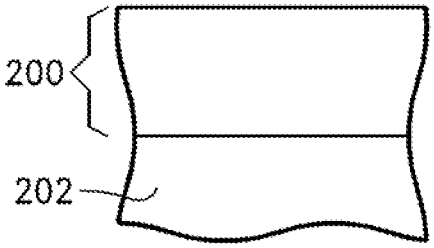


FIG. 4C

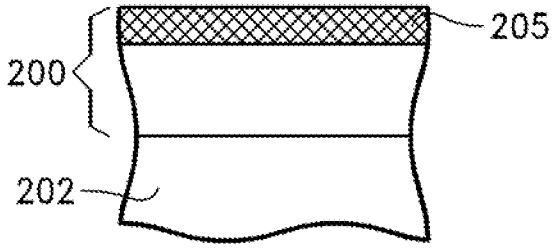


FIG. 4D

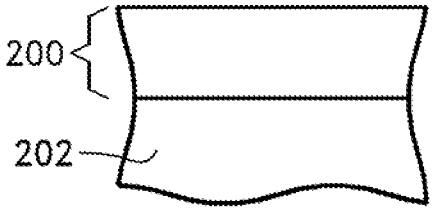


FIG. 4E

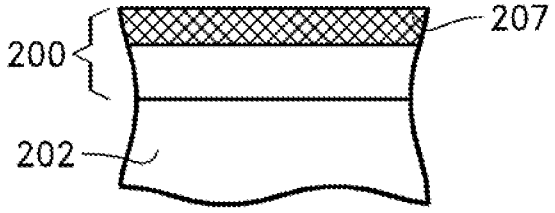


FIG. 4F

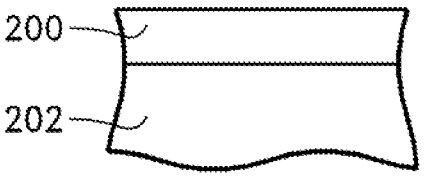


FIG. 4G

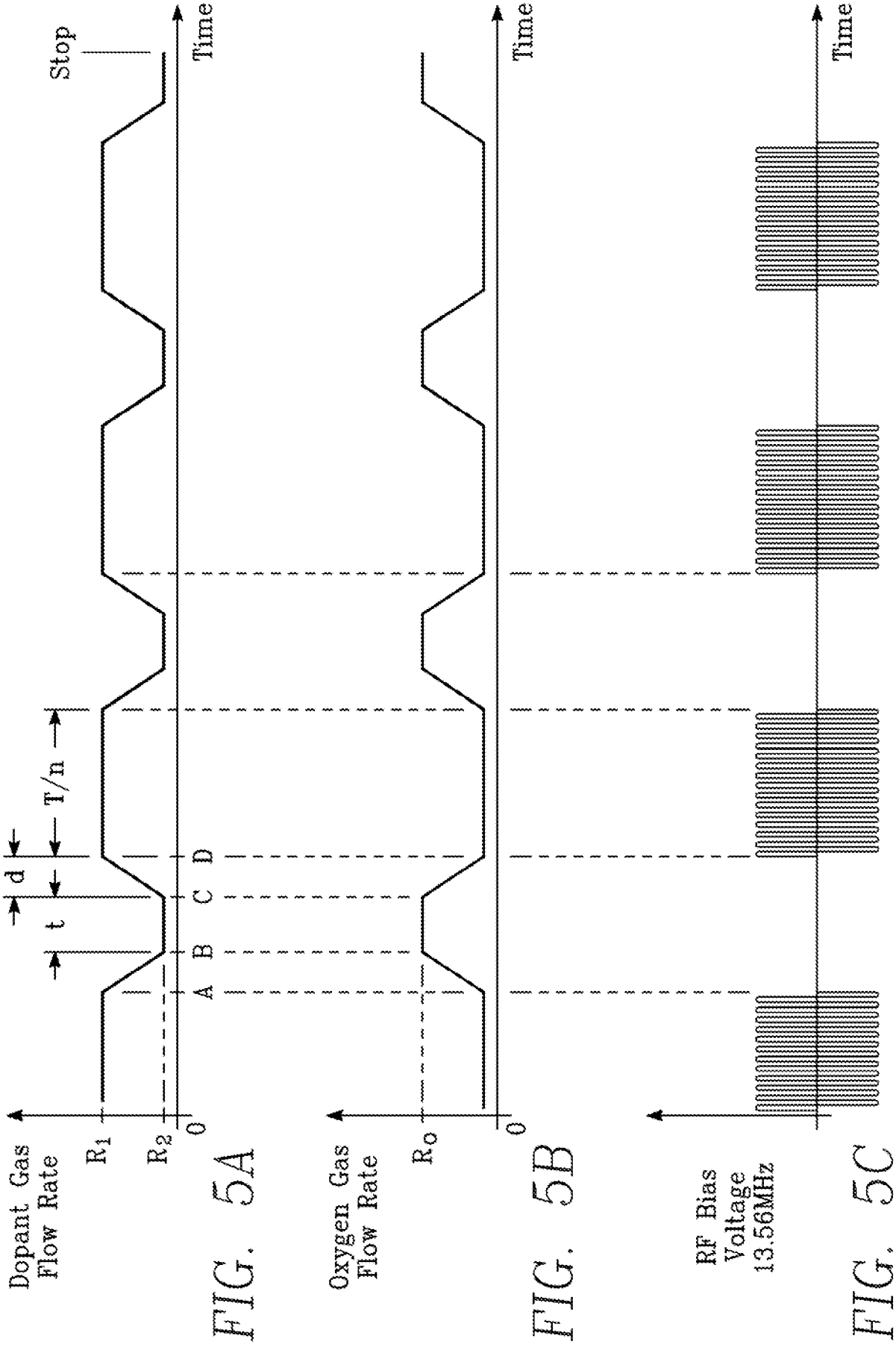


FIG. 5A

FIG. 5B

FIG. 5C

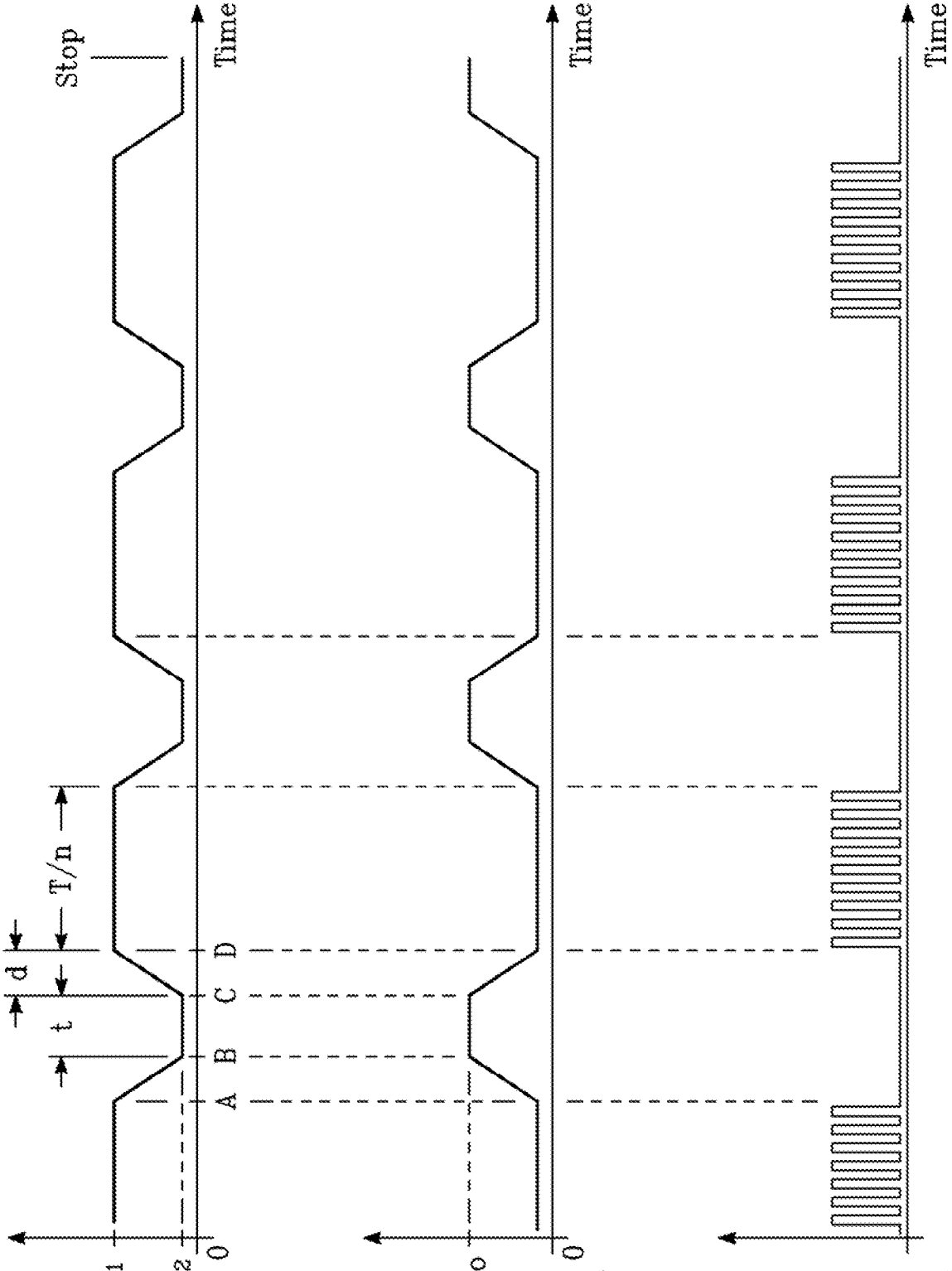


FIG. 6A

FIG. 6B

FIG. 6C